Notice of Allowability	Application No.	Applicant(s)
	10/604,341	CHEN, YINAN
	Examiner	Art Unit
	Jennifer M. Kennedy	2812
The MAILING DATE of this communication ap All claims being allowable, PROSECUTION ON THE MERITS I herewith (or previously mailed), a Notice of Allowance (PTOL-8 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT of the Office or upon petition by the applicant. See 37 CFR 1.3	S (OR REMAINS) CLOSED in t 5) or other appropriate commun RIGHTS. This application is sul	his application. If not included
 This communication is responsive to <u>the case filed 7/14/1</u> The allowed claim(s) is/are <u>1-6</u>. 		
3. The drawings filed on 14 July 2003 are accepted by the I		
4. Acknowledgment is made of a claim for foreign priority	under 35 U.S.C. § 119(a)-(d) or	(f).
a) All b) Some* c) None of the:		
1. Certified copies of the priority documents ha		
2. Certified copies of the priority documents have		
3. Copies of the certified copies of the priority d	locuments have been received in	n this national stage application from the
International Bureau (PCT Rule 17.2(a)).		
* Certified copies not received: 5. Acknowledgment is made of a claim for domestic priority reference was included in the first sentence of the specific (a) The translation of the foreign language provisional 6. Acknowledgment is made of a claim for domestic priority in the first sentence of the sent	cation or in an Application Data application has been received.	Sheet. 37 CFR 1.78.
in the first sentence of the specification or in an Application	on Data Sheet. 37 CFR 1.78.	·
Applicant has THREE MONTHS FROM THE "MAILING DATE" obelow. Failure to timely comply will result in ABANDONMENT of the complex	of this communication to file a ref f this application. THIS THREE	ply complying with the requirements noted
7. A SUBSTITUTE OATH OR DECLARATION must be subminformal patent application (PTO-152) which give	mitted. Note the attached EXAM ves reason(s) why the oath or de	INER'S AMENDMENT or NOTICE OF eclaration is deficient.
 8. CORRECTED DRAWINGS (as "replacement sheets") mu (a) including changes required by the Notice of Draftsper 1) hereto or 2) to Paper No 	ust be submitted. rson's Patent Drawing Review (PTO-948) attached
(b) including changes required by the proposed drawing	correction filed, which h	as been approved by the Examiner.
(c) including changes required by the attached Examiner	r's Amendment / Comment or in	the Office action of Paper No
Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in	1.84(c)) should be written on the of the margin according to 37 CFR 1	drawings in the front (not the back) of I.121(d).
 DEPOSIT OF and/or INFORMATION about the deport attached Examiner's comment regarding REQUIREMENT FOR 	osit of BIOLOGICAL MATERI THE DEPOSIT OF BIOLOGICA	AL must be submitted. Note the L MATERIAL.
Attachm nt(s)		
1⊠ Notice of References Cited (PTO-892)	5□ Notice of Inform	al Patent Application (PTO-152)
 2 Notice of Draftperson's Patent Drawing Review (PTO-948) 3 Information Disclosure Statements (PTO-1449 or PTO/SB/08), Paper No. 	6☐ Interview Summ	ary (PTO-413), Paper No.
	8), 7⊠ Examiner's Ame	
4☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	8⊠ Examiner's State 9⊟ Other	ement of Reasons for Allowance

Application/Control Number: 10/604,341

Art Unit: 2812

EXAMINER'S AMENDMENT

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

The application has been amended as follows:

In claim 1, line 8, "title" has been changed to tilt.

In claim 4, line 8, "title" has been changed to tilt.

The following is an examiner's statement of reasons for allowance: the prior art, either singly or in combination, fails to anticipate or render obvious, the method, including the limitations of forming a dielectric layer on the first sidewall, the second sidewall and the bottom of the trench in a substrate layer, performing a tilt angle ion implantation process to dope ions into the first dielectric layer on the first sidewall and on the bottom, but not dope ions into the first dielectric layer on the second sidewall, selectively etching away the doped first dielectric layer on the first sidewall and on the bottom in combination with the other limitations of the claim.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Jennifer M. Kennedy whose telephone number is (703) 308-6171. After February 3, 2003, the examiner can be reached at (571) 272-1672. The examiner can normally be reached on Mon.-Fri. 8:30-5:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, John Niebling can be reached on (703) 308-3325. After February 3, 2003 the examiner's supervisor can be reached at (571) 272-1679. The fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

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Supervisory Patent Examiner Technology Center 2800